

EUV Mask Standards Roadmap

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February 22, 2004

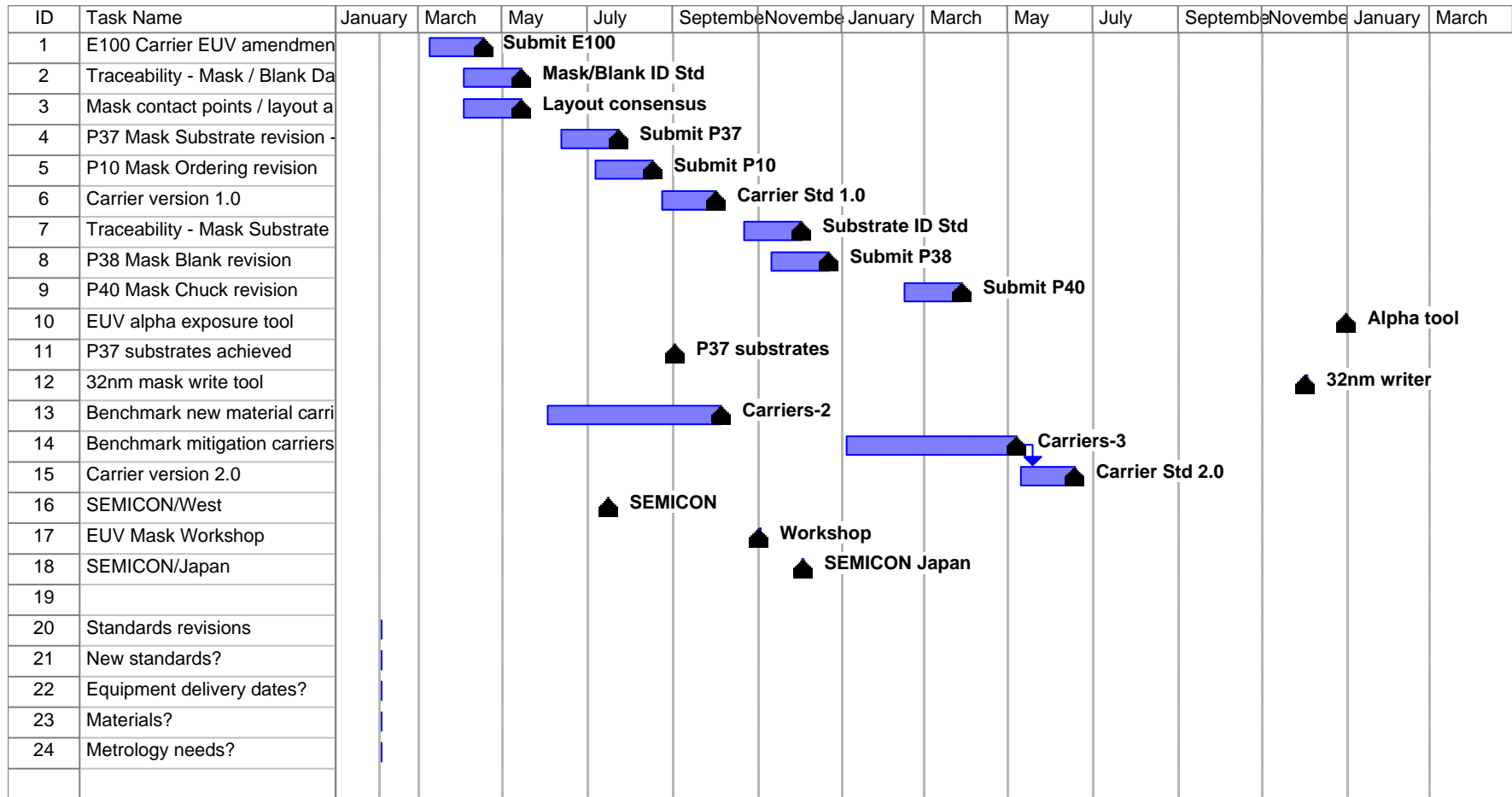
Background

- **Initial IEUVI Mask TWG meeting held in Antwerp in Oct. '03.**
- **Assigned to develop a roadmap for standards and milestones related to EUV masks.**
- **Guidance for coordinating development and performance of equipment, materials, and standards.**

Roadmap Draft

- **Draft roadmap distributed to TWG members in January.**
- **Intended to provide support for one alpha exposure tool in December 2005.**
- **TWG will review, modify, and ratify the roadmap in session later today.**

EUV Mask Standards Roadmap



Standards

- **SEMI P37, EUV mask substrate.**
- **SEMI P38, EUV mask blank.**
- **SEMI P40, EUV mask chucking.**
- **SEMI P10, mask ordering.**
- **Traceability for mask/blank and for substrate.**
- **Carrier approach.**
- **Layout / handling areas.**